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R. Stuber

35.G2732

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
MASATO MURAKI, ET AL.) : Examiner: Unassigned
Application No.: 09/708,590) : Group Art Unit: 2881
Filed: November 9, 2000) :
For: CORRECTING METHOD FOR) : February 20, 2001
CORRECTING EXPOSURE DATA :
USED FOR A CHARGED)
PARTICLE BEAM EXPOSURE :
SYSTEM)

Commissioner for Patents
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

Sir:

To comply with the duty of disclosure under 37 CFR 1.56 and in accordance with the practice under 37 CFR 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449 Form. Copies of the listed documents are also enclosed.

RECEIVED
FEB 22 2001
TECHNOLOGY CENTER 2800

(1) The Parikhh article is discussed on page 2 of the specification and discusses corrections to proximity effects in electron beam lithography.

(2) The Pavkovich article is also discussed on page 2 of the specification and discusses proximity effect correction calculations by the integral equation approximate solution method.

Applicants request that the Examiner consider the cited information and return an initialed copy of the enclosed PTO-1449 Form indicating that such information has been considered.

Applicants believe that no fees should be incurred in connection with filing this paper. Nevertheless, the Commissioner is authorized to charge Deposit Account No. 06-1205 should any fees be associated herewith. A duplicate of this paper is enclosed for this purpose.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010.

All correspondence should be directed to our address listed below.

Respectfully submitted,



Attorney for Applicants
Registration No. 33,326

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